

axis of said shaft, and wherein said planar upper surface substantially surrounds a chimney.

46. (Amended) The two-stage endosseous dental implant system according to Claim 17, wherein said abutment-implant interface has a substantially planar upper surface substantially surrounding said means for connecting, and wherein said upper planar surface is approximately 90° to the longitudinal axis of said shaft.

53. (Amended) The one-stage endosseous dental implant system according to Claim 24, wherein said abutment has a substantially planar upper surface substantially surrounding a chimney, and wherein said upper planar surface is approximately 90° to the longitudinal axis of said shaft.

A marked up version of the above claims can be found in *Appendix A*.

REMARKS

Applicant will sequentially address the issues raised by the Examiner. The paragraph numbers correspond to those of the Examiner's for ease of reference.

1. The Examiner requested that a statement be entered into the specification referencing the prior patent application. The Examiner's attention is directed to the transmittal form for this Continuation application. Paragraph number 3 of the continuation transmittal amended the specification to include a reference to the prior parent application. In light of the above, it is respectfully requested that this amendment be entered.

2. The Examiner objected to the numbering of the claims. The Applicant thanks the Examiner for renumbering the claims accordingly.

3. The Examiner objected to claims 35, 40, 43, and 53 because of an informality, namely that "900" should read --90°--. Claims 35, 40, 43, and 53 have been amended to correct this typographical error.